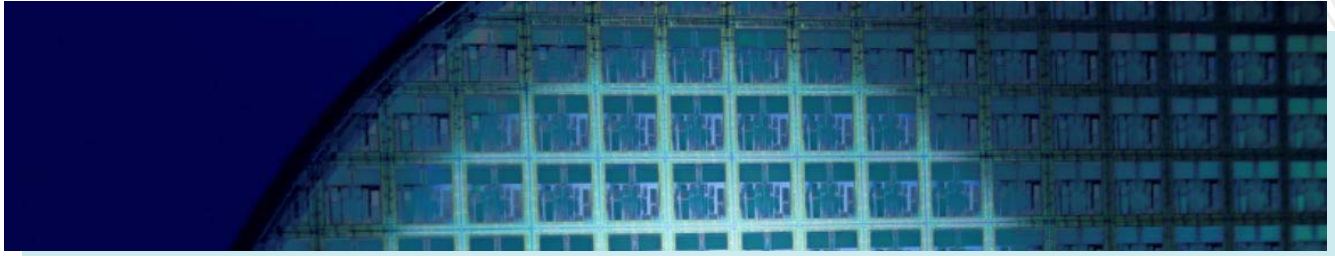


XENON DIFLUORIDE (XeF₂)



ELECTRONIC GRADE

TOTAL PURITY ≥99.999%



Xenon DiFluoride (XeF₂) is a very efficient and selective etch gas, used in MEMs applications. XeF₂ shows very high selectivity of silicon vs. photoresist, silicon dioxide (SiO₂), silicon nitride (Si₃N₄), aluminum, chromium (Cr) and TiN.

SPECIFICATIONS

Aluminum (Al)	≤ 2 ppm
Calcium (Ca)	≤ 1 ppm
Cobalt (Co)	≤ 1 ppm
Chromium (Cr)	≤ 3 ppm
Copper (Cu)	≤ 2 ppm
Iron (Fe)	≤ 8 ppm
Potassium (K)	≤ 1 ppm
Lithium (Li)	≤ 1 ppm
Magnesium (Mg)	≤ 1 ppm
Manganese (Mn)	≤ 1 ppm
Molybdenum (Mo)	≤ 1 ppm
Sodium (Na)	≤ 1 ppm
Nickel (Ni)	≤ 5 ppm
Total Metals	≤ 10 ppm

PHYSICAL PROPERTIES

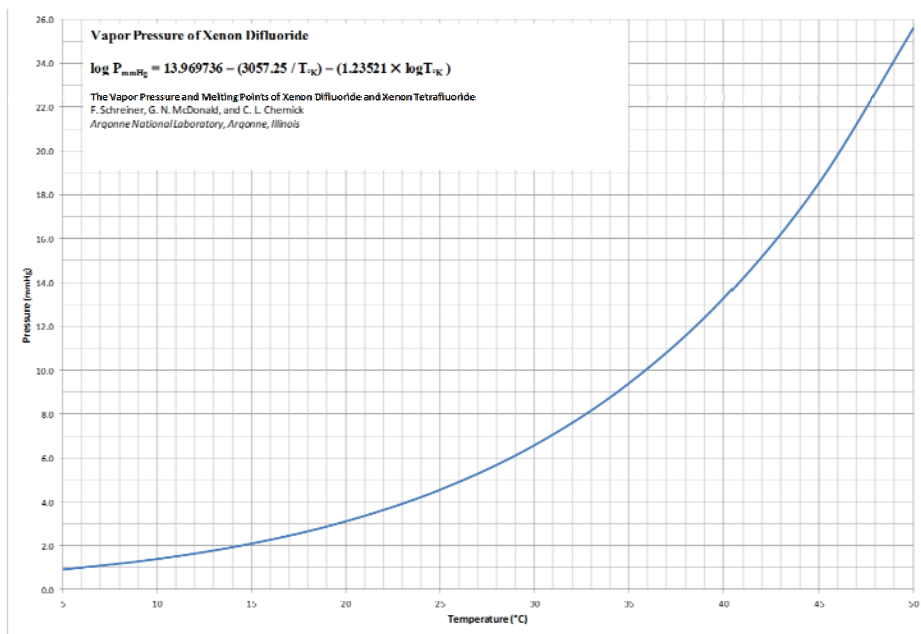
Formula	XeF ₂	Density	4.32kg/L
Molecular Weight	169.29	Vapor Density	ND
Melting Point	129.4° C	Vapor Pressure	4 torr @ 25° C
TLV	2.5 mg/m3 as fluoride		

DISTINGUISHING FEATURES

XeF₂ etching is a dry process, so no drying is needed, which helps to avoid the sticking issues that often plague wet release processes.

STANDARD PACKAGE INFORMATION

Material Number	191596	182680	186586
Cylinder Size (L)	1 liter	1 liter	3 liter (pneumatic valve)
Fill Weight (KG)	0.5 KG	2 KG	5 KG
Valve Connection	¼" male VCR	¼" male VCR	DISS 716
Cylinder Dimensions without valve—Diameter x height (cm)	8 x 30	8 x 30	11 x 41
Cylinder Dimensions without valve—Diameter x height (in)	3.1 x 11.8	3.1 x 11.8	4.3 x 16.14



**VAPOR PRESSURE CURVE FOR
XENON DIFLUORIDE**



For more information, please contact us at:

VERSUM MATERIALS, LLC
VERSUMMATERIALS.COM

The information contained herein is offered without charge for use by technically qualified personnel at their discretion and risk. All statements, technical information and recommendations contained herein are based on tests and data which we believe to be reliable, but the accuracy or completeness thereof is not guaranteed and no warranty of any kind is made with respect thereto.